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(54) **MODIFIED DICYCLOPENTADIENE-BASED RESIN**

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(58) **Field of Classification Search**
None
See application file for complete search history.

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(57) **ABSTRACT**

A modified dicyclopentadiene-based resin is provided. The modified dicyclopentadiene-based resin is formed from a dicyclopentadiene-based resin having an amino group, a phenol and a polyoxymethylene by a cyclization reaction. The dicyclopentadiene-based resin having an amino group is formed by nitration reaction and hydrogenation reaction of dicyclopentadiene phenolic resin.

10 Claims, No Drawings